

**IN THE CLAIMS:**

This listing of claims will replace all prior versions, and listings, of claims in the application:

1-27. (Canceled)

28. (Currently amended) An apparatus for manufacturing photomask blanks comprising:  
a substrate holder for holding a square shaped substrate, said holder having a rotation  
mechanism for rotating the substrate around its center axis; and  
a target placed in an opposed position with a center axis of said target deviating from the  
center axis of said substrate held by said substrate holder.

~~An apparatus according to claim 27,~~ wherein the target is placed so that the opposed surfaces  
of the target and the substrate form a predetermined angle therebetween.

29. (Currently amended) An apparatus for manufacturing photomask blanks comprising:  
a substrate holder for holding a square shaped substrate, said holder having a rotation  
mechanism for rotating the substrate around its center axis; and  
a target placed in an opposed position with a center axis of said target deviating from the  
center axis of said substrate held by said substrate holder;

~~An apparatus according to claim 27, further comprising:~~  
means for detecting a rotation position of the substrate; and  
means for turning OFF an electric discharge to finish film formation when the substrate has  
completed an integral number of rotations from the position when turning ON the electric

discharge to start film formation, so as to finish film formation at the position of the same rotation angle as the starting position of the film formation.